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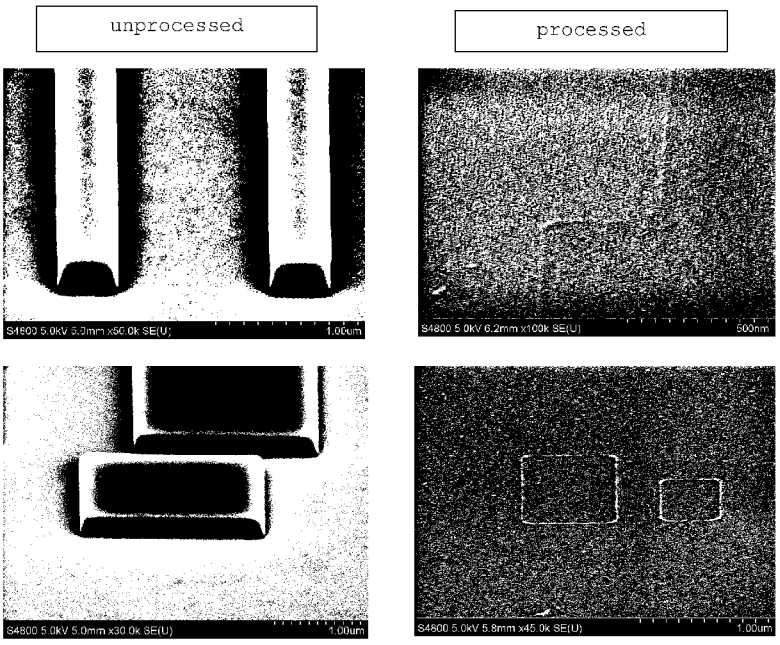
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(54) Title: METHOD FOR TREATMENT OF SUBSTRATES AND TREATMENT COMPOSITION FOR SAID METHOD

Fig. 1



(57) Abstract: A mixture of perhalogenic acid and sulfuric acid is unexpectedly stable at high temperatures and is effective in stripping photoresists, including difficult to treat ion-implanted photoresists, with short processing times. In use, no decomposition of the mixture is observed up to a temperature of 145°C. In the mixture, the sulfuric acid is highly purified and has a concentration of 96 wt% or greater. The perhalogenic acid is preferably H_5IO_6.

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